

Akulon® F136-C1 | PA6 | Envalior

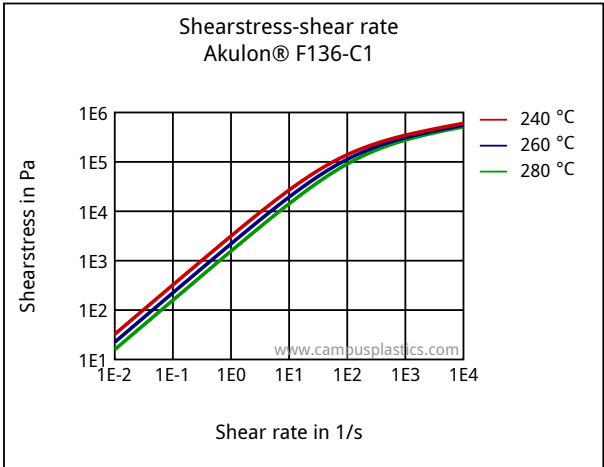
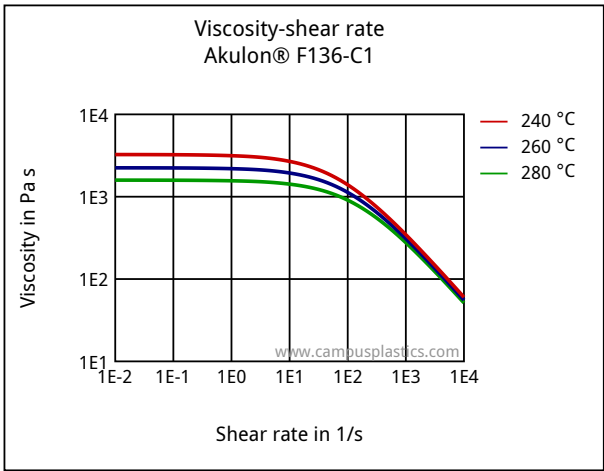
ISO 1043 PA6

Film Properties	Value	Unit
Stress at yield, parallel	31	MPa
Maximum stress, parallel	83	MPa
Maximum strain, parallel	350	%
Trouser tear resistance, parallel	32	N/mm
Dynamic coefficient of friction	1	-
Wear loss, 1000 cycles, 5°C/85%r.h.	35	g/(m ² *km)

Oxygen transmission rate, 23°C/0%r.h.
Oxygen transmission rate, 23°C/85%r.h.
Type of extrusion
Thickness of specimen

27 cm³/((m²*d*bar)
39 cm³/((m²*d*bar)
cast -
0.05 mm

Diagrams



Characteristics

Processing

Film Extrusion, Other Extrusion

Delivery form

Pellets

Additives

Lubricants

Regional Availability

Europe, Asia Pacific

Other text information

Film extrusion

Processing of Akulon® Film Grades

Chemical Media Resistance

Alcohols

Methanol (23°C)

Ethanol (23°C)

Hydrocarbons

Toluene (23°C)

Acetone (23°C)

Ethers

Diethyl ether (23°C)

Other

Ethyl Acetate (23°C)

Water (23°C)

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